



PATENT  
Attorney's Docket No. 015675P326

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#19/B  
Jade  
10/27/02

In re Application of: )  
Andre Leycuras ) Examiner: Bret P. Chen  
Serial No.: 09/601,109 ) Art Group: 1762  
Filed: October 16, 2000 )  
For: CHEMICAL VAPOR )  
DEPOSITION REACTOR AND )  
PROCESS )

Assistant Commissioner for Patents  
Washington, D.C. 20231

AMENDMENT AND RESPONSE TO OFFICE ACTION

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Sir:

In connection with the Request for Continuing Examination under 37 CFR §1.114,  
Applicant respectfully requests entry of the following amendments and reconsideration in view of  
the following remarks.

IN THE CLAIMS

Presented below are all the amended claims in clean unmarked form. The claims, in  
marked-up form, are presented as an attachment.

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TC 1700

- 1        1. (Amended) Process for a chemical vapor deposition of layers of a material on a  
2        substrate which extends generally in a plane, comprising:  
3              placing the substrate in a horizontal duct made of a refractory material;  
4              heating independently an upper and lower wall of the duct by a first and second heater, the  
5        first and second heater extending above and below the substrate, outside the duct;  
6              heating independently an upper and lower surface of the substrate by radiation of heat from  
7        at least one wall of the duct raised to a temperature substantially higher than ambient temperature;